IN THE UNITED STATES DISTRICT COURT FOR THE WESTERN DISTRICT OF TEXAS WACO DIVISION

THE TRUSTEES OF PURDUE UNIVERSITY,

Plaintiff,

V.

CIVIL ACTION NO. 6:21-CV-00727-ADA

STMICROELECTRONICS N.V., STMICROELECTRONICS INTERNATIONAL N.V., and STMICROELECTRONICS, INC,

Defendants.

JURY TRIAL DEMANDED

JOINT CLAIM CONSTRUCTION STATEMENT

Pursuant to the Scheduling Order (Dkt. 45), Plaintiff The Trustees of Purdue University ("Purdue") and Defendant STMicroelectronics, Inc.¹ submit this Joint Claim Construction Statement.

I. DISPUTED CLAIM TERMS FROM U.S. PATENT NO. 8,035,112

Claim Term ²	Claim(s)	Plaintiff's Construction	Defendant's Construction
"a second, thicker oxide layer"	1	"layer of oxide that is on the tops and sides of each gate and that is thicker than the layer of oxide below each gate"	"an oxidation layer formed, created, or grown by reacting the gate, thicker than the first oxide layer"

Purdue states that STNV was specifically named in claim construction exchanges except in the briefing. *See* Dkts. 70-6 & 70-7. ST states that each of Dkts. 70-6 & 70-7 explained that "STNV is not subject to the Court's jurisdiction, as detailed in its Motion to Dismiss [ECF 38]."

¹ Purdue also names as defendants STMicroelectronics N.V. ("STNV") and STMicroelectronics International N.V. ("ST Int'l"). STNV is not subject to the Court's jurisdiction, as detailed in its Motion to Dismiss [ECF 38], and ST Int'l has not yet been served in this case and therefore is not properly before the Court or subject to the Court's jurisdiction.

² For the disputed terms of this patent, Purdue proposes construing the longer phrases for clarity and context, i.e., "a second, thicker oxide layer over said top surface and sidewall of each of said first gate"/ "a gate oxide layer thicker than said substrate surface oxidation layer, over said tops and sides of each of said gates".

Claim Term ²	Claim(s)	Plaintiff's Construction	Defendant's Construction
"a gate oxide layer"	6	"layer of oxide that is on the tops and sides of each gate and that is thicker than the layer of oxide below each gate"	"an oxidation layer formed, created or grown by reacting the gate"

II. DISPUTED CLAIM TERMS FROM U.S. PATENT NO. 7,498,633

Claim Term	Claim(s)	Plaintiff's Construction	Defendants' Construction
"double-implanted metal-oxide semiconductor field- effect transistor"	9	The preamble is not limiting. In the alternative only, "double-implanted" is not limiting. ³	The preamble is limiting.
"less than about three micrometers"	9	Plain and ordinary meaning, no construction necessary.	Indefinite

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 $^{^3}$ ST notes that Purdue previously offered that "[i]n the alternative only, 'metal-oxide semiconductor field-effect transistor is limiting."

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By: /s/Mark D. Siegmund

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CERTIFICATE OF SERVICE

Pursuant to the Federal Rules of Civil Procedure and Local Rule CV-5, I hereby certify that, on April 14, 2022, all counsel of record who have appeared in this case are being served with a copy of the foregoing via the Court's CM/ECF system.

/s/ Mark D. Siegmund
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